IN THE SPECIFICATION:

Please amend the specification as follows:

Please substitute the paragraph beginning at page 2, line 1, with the following.

-- The projection exposure apparatus has been requested to expand its exposure area with recent demands for a larger LCD substrate. FIG. 13 is a schematic view of a principal part in a conventional scanning exposure apparatus of a common mirror-projection type. In FIG. 13, 1 denotes a mask, 2 a mask stage for scanning the mask 1, [[4]] 51-53 a projection optical system, [[5]] 3 a plate such as a glass plate, and [[6]] 4 a plate stage for scanning the plate [[5]] 3. UV reactive photoresist is applied onto a surface of the plate [[5]] 3. Reference numeral ~~13 is~~ 11 represents arc-shaped illumination light from an illumination system [[7]] not shown. --

Please substitute the paragraph beginning at page 2, line 13, with the following.

-- As illustrated, the illumination system 7 generates the arc-shaped illumination light ~~13~~ 55 using an arc-shaped aperture or a slit aperture arranged just before the mask 1 or at a position that is optically conjugate with the mask 1. Alternatively, use of an optical element such as a cylindrical lens would also provide similar arc-shaped illumination light. --

Please substitute the paragraph beginning at page 2, line 20, with the following.

-- ~~11 denotes an~~ An XYZ coordinate system is not shown. The illuminated scanning exposure apparatus aligns a longitudinal direction of the arc-shaped illumination light 13 with the X-axis direction, a transverse direction or a scan direction of the mask stage 2, and the plate stage

6 with the Y-axis direction, and a direction perpendicular to the XY plane with a Z-axis direction. --